MECHANICAL LOSS IN SILICA SUBSTRATES

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Introduction



- Thermal noise from internal degrees of freedom of interferometer test masses is a limiting noise source in the sensitive mid-frequency bands.
- Must quantify mechanical loss in both Silica Substrate and Coating Layers.





History: Old Formalism for Loss

"Thermal noise in interferometric gravitational wave detectors due to dielectric optical coatings" [Harry, et al., Classical & Quantum Gravity, 19 (2002) 897-917]



- Derives thermal noise power spectrum in terms of $\phi_{substrate}$ and coating losses ϕ_{\parallel} and ϕ_{\perp} .
- Assuming $\sigma = \sigma' = 0$,

$$S_{x}(f) = \frac{1}{wY} \frac{2k_{B}T}{f\pi^{3/2}} \left\{ \phi_{substrate} + \frac{1}{\sqrt{\pi}} \frac{d}{w} \left(\frac{Y'}{Y} \phi_{\parallel} + \frac{Y}{Y'} \phi_{\perp} \right) \right\}$$

• Finding ϕ_{\parallel} ,



- Finding ϕ_{\perp} ...???
- Assumes $\phi_{\parallel} = \phi_{\perp}$



Impetus: New Formalism for Loss

"Brownian Thermal Noise in Multilayer Coated Mirrors" [Hong, et al, LIGO-G1200614-v1, Submitted to Phys. Rev. D]



vsis to

substrate

- ϕ_{\parallel} and ϕ_{\perp} formalism of Harry, et al. can lead to erroneous values require new formalism.
- When applying a force with known pressure profile:

$$U_{coating} = U_B + U_S = \iiint_{coating} \left(\frac{K}{2} \Theta^2 + \mu \Sigma_{ij} \Sigma_{ij} \right) dV$$

New formalism for mechanical loss in coating starting from elastic energy • contained in *bulk energy* U_B and *shear energy* U_S . loss in coating

$$\phi_{coated} = \frac{U_{substrate}}{U_{Total}} \phi_{substrate} + \frac{U_B}{U_{Total}} \phi_B + \frac{U_S}{U_{Total}} \phi_S$$

$$\phi_{substrate} = \frac{U_{B,Sub}}{U_{Total}} \phi_{B,Sub} + \frac{U_{S,Sub}}{U_{Total}} \phi_{S,Sub}$$
• Without a coating, should be able to extend this analysis to bulk and shear loss in



Measurement Techniques: FEA



▲ 3.6802

• A finite element analysis of an uncoated silica sample is used to find its approximate resonance frequencies.







Eigenfrequency=9353.680051 Surface: Total displacement (m)





Measurement Techniques: Hanging Sample







Measurement Techniques: Bell Jar Upgrade











Measurement Techniques: Birefringence Sensor



LIGO



Measurement Techniques: Mode Hunting





Network/Signal Analyzer



Matlab + Waveform Generator + Lockin Amplifer allows for complete control of all sweep parameters: input filter bandwidth, step time and step size down to 1μ Hz.

Matlab Instrument Control



Measurement Techniques: Ringdowns







Measurement Techniques: Q Results



Sample	Mode Freq [Hz]	Q
Sample 24	2706.5	2.009×10 ⁷
	6162.4	1.47×10 ⁷
	9445.8	5.49×10 ⁶
Sample 25	2699.2	1.9×10 ⁷
	6149.6	1.89×10 ⁷
	9438.3	1.326×10 ⁷
	10,612.5	7.66×10 ⁶
Sample 26	2758.1	1.911×10 ⁷
	4163.2	8.88×10 ⁶
	37,039.1	1.488×10 ⁷



Analysis: Return to FEA with New Formalism



• Elastic energy can be divided into *bulk energy* U_B and *shear energy* U_S when applying a force with a known pressure profile,

$$U_{Total} = U_{B,Sub} + U_{S,Sub} = \iiint_{Sub} \left(\frac{K}{2}\Theta^{2} + G\Sigma_{ij}\Sigma_{ij}\right)dV$$

Bulk:
$$D = S_{11} + S_{22} + S_{33}$$

$$\psi_{Substrate} = \underbrace{\bigcup_{B,Sub}}_{Sub} \phi_{B,Sub} + \underbrace{\bigcup_{S,Sub}}_{U_{Total}} \phi_{S,Sub}$$



Analysis: FEA Energy Ratios







Preleminary Results



• Bulk and Shear loss can be then be calculated:

$$\begin{bmatrix} \phi_{a} \\ \phi_{b} \end{bmatrix} = \begin{bmatrix} \frac{U_{a,Bulk}}{U_{a,Tot}} & \frac{U_{a,Shear}}{U_{a,Tot}} \\ \frac{U_{b,Bulk}}{U_{b,Tot}} & \frac{U_{b,Shear}}{U_{b,Tot}} \end{bmatrix} \begin{bmatrix} \phi_{Bulk} \\ \phi_{Shear} \end{bmatrix}$$

Sample 26	ϕ_{Bulk}	ϕ_{Shear}
	1.96×10^{-7}	4.24×10^{-8}
	1.67×10^{-7}	6.66×10^{-8}

• Note that we lose frequency information! (or it's buried, at least)



"Frequency and surface dependence of mechanical loss in fused silica"

[Penn, et al., Physics Letters A, 352 (2006) 3-6]



- Shows that mechanical loss of silica substrate $\phi_{substrate}$ depends on frequency and surface-to-volume ratio.

$$\phi\left(f,\frac{V}{S}\right) = \phi_{surf} + \phi_{vol} + \phi_{th}$$
$$= C_1 \left(\frac{V}{S}\right)^{-1} + C_2 \left(\frac{f}{(1\text{Hz})}\right)^{C_3} + C_4 \phi_{th}$$
$$Type \quad C_1 (pm) \quad C_2 (\times 10^{-11}) \quad C_3 \quad C_4$$
Suprasil 2 12.1 1.18 0.77 0.61



 Frequency dependence of loss agrees well with results of modeling asymmetric double-well potential in Si-O-Si bond angle. [Weidersich, et al., Phys. Rev. Lett. 84 (2000) 2718]

Туре	C ₃
Suprasil 300	≈0.75





Still Lots to Do!



- Frequency Dependence $\phi(f)$:
 - More Data Pairs easier to probe higher order modes with wideband HV Amplifier and computer control
 - Design second sample with different energy ratios, but similar mode frequencies
- Include dependence of loss on Surface to Volume ratio in analysis $\phi\left(\frac{V}{s}\right)$
- Include Shear/Bulk loss in Surface analysis
- Compare to other theoretical models (Hai Ping Cheng, etc.)
- Annealing
- More modes, reanalyzing old data

$$\phi\left(f,\frac{V}{S}\right) = \phi_{surf} + \phi_{vol} \quad \longrightarrow \quad \phi\left(f,\frac{V}{S}\right) = \phi_{surf,B} + \phi_{surf,S} + \phi_{vol,B} + \phi_{vol,S}$$